Amendments To The Claims:

This listing of claims will replace all prior claim lists in this application.

Listing of Claims:

Amendments to the Claims:

This listing of claims will replace all prior version and listings of claims in the application:

Listing of Claims:

1. (Currently amended) A method of processing a workpiece, the method comprising the steps of:

fastening a workpiece to be processed to a work carrier by means of a solid that is applied in liquefied form,

wherein the work carrier comprises a porous material including a plurality of pores at least a portion of which are interconnected, and

wherein the plurality of pores are configured to accommodate a portion of the liquefied solid upon application of vacuum pressure to the work carrier.

- 2. (Previously presented) The method as claimed in claim 1, wherein the work carrier comprises a gas-permeable work carrier.
- 3. (Currently amended) The method as claimed in claim 1-or 2, wherein the solid functions to separate the workpiece and the work carrier, wherein the workpiece is released by means of a solvent.
- 4. (Currently amended) The method as claimed in claim 3, wherein a <u>the</u> work carrier <u>comprises a porous material</u> which is permeable to said solvent is <u>used</u>.
- 5. (Currently amended) The method as claimed in claim 1, wherein the porous material is <u>comprises</u> a ceramic, a glass, a glass ceramic, a metal, a sintered metal, a metal ceramic or a sintered material.

- 6. (Currently amended) The method as claimed in claim 1, wherein the workpiece is thinned further comprising thinning the workpiece on the work carrier.
- 7. (Previously presented) The method as claimed in claim 1, wherein the solid comprises a material selected from a group consisting of: wax, adhesive, a plastic material, or a double-sided adhesive tape.
- 8. (Previously presented) The method as claimed in claim 1, wherein the workpiece contains a semiconductor material.
- 9. (Previously presented) The method as claimed in claim 1, wherein the solid fills at least a portion of an intermediate space between the workpiece and the work carrier.
- 10. (Currently amended) A work carrier for processing a workpiece, said work carrier comprising a porous material including a plurality of pores at least a portion of which are interconnected, wherein the plurality of pores are configured to accommodate a portion of a liquefied solid upon application of vacuum pressure to the work carrier.
- 11. (Previously presented) The work carrier as claimed in claim 10, wherein the diameter of the work carrier is equal to the diameter of the semiconductor wafer.
- 12. (Currently amended) The method as claimed in claim 1 wherein <u>fastening</u> the workpeice comprises generating a vacuum is generated at the work carrier for the <u>fastening</u>.
- 13. (Previously presented) The method as claimed in claim 12 wherein the vacuum is generated after the application of the solid in liquefied form and before the hardening of the solid.
- 14. (Previously presented) The method of claim 4 wherein, to separate the workpiece and work carrier, said solvent penetrates into passages from a pore or from the plurality of pores through the work carrier up to the solid.

- 15. (Currenltly amended) The method of claim 14 wherein the reparations separation of the workpiece from the work carrier preferably comprises reparation separation by the generation of a positive pressure on a side of the work carrier which is remote from the workpiece.
- 16. (Previously presented) The method as claimed in claim 1, wherein the average pore size has a value of between 20µm and 500µm, and wherein the porosity of the porous material has a value of between 20% and 50%.
- 17. (Previously presented) The method as claimed in claim 1, wherein the value of the open porosity of the porous material lies between 10% and 60%.
- 18. (Previously presented) The method as claimed in claim 1, wherein a portion of the plurality of pores include pore passages, wherein the pore passages comprise at least 10% of the pore volume, and wherein the pore passage traverse the porous material from a top side to a rear side of the carrier.
- 19. (Previously presented) The method as claimed in claim 1, wherein the porous material comprises a ceramic material manufactured according to one of German Institute Standard DIN 51056, 1985 or European Standard 623-2, 1992, and wherein the pores are arranged irregularly.
- 20. (Previously presented) The method as claimed in claim 1, wherein the average pore size ranges from 50μm to 100μm.
- 21. (Previously presented) The method as claimed in claim 1, wherein the value of the open porosity of the porous material lies between 20% and 50%.
- 22. (Previously presented) The work carrier as claimed in claim 10, wherein the plurality of pores comprise a branched pore network within the work carrier.
- 23. (Previously presented) The work carrier as claimed in claim 10, wherein a portion of the plurality of pores include pore passages, wherein the pore passages

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comprise at least 10% of the pore volume, and wherein the pore passages traverse the work carrier from a top side to a rear side of the work carrier.